ABSTRACT

SUBSTRATE CLEANING SYSTEM, SUBSTRATE CLEANING METHOD, SUBSTRATE CLEANING PROGRAM, AND PROGRAM RECORDING MEDIUM

A substrate cleaning system according to the present invention comprises cleaning devices, and a controller for controlling the driving of the cleaning devices in accordance with driving recipes predetermined. The controller prioritizes the cleaning devices, calculates, on the basis of a driving recipe for a cleaning device having a higher priority and a driving recipe for a cleaning device having a lower priority, a time in which the two cleaning devices can interfere with each other, and sets the calculated time as a waiting time. The cleaning device having the higher priority is made to start cleaning a substrate from a predetermined cleaning-starting position, while the cleaning device having the lower priority is kept waiting in a predetermined waiting position. When or after the waiting time has elapsed since the cleaning device having the higher priority started cleaning, the cleaning device having the lower priority is made to move from the waiting position and start cleaning the substrate.

FIG. 9



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